

The plasma technological device comprises a vacuum chamber with the system of intake and control of gases, in the upper part of which dielectric window with an antenna is axially located, this is connected to the HF generator through a matching device, in the lower part of the chamber holder with lining is situated, this can be connected to a power source, at outside the chamber is surrounded with a magnetic system of two solenoid elements. In the space between the dielectric window and the liner a cylindrical hollow electrode is axially mounted, the diameter of this is determined from the relationship. At that, its height is determined by the shortened wavelength of fundamental frequency in plasma, and the distance between the liner plane and the output cut of the cylindrical hollow electrode is set by the relationship.